

Abstract of the Disclosure***POLISHING APPARATUS OF SUBSTRATE END FACE AND
POLISHING DETERMINING METHOD***

To provide a substrate end face polishing apparatus in accordance with an adaptive control incorporating a depth of an abrasion groove of a polishing wheel into a compensation element and having high reliability, together with a method of determining whether the polishing of the substrate is good or bad, the substrate end face polishing apparatus is provided with a polishing wheel for polishing an end face of the substrate, a rotational driving means of the polishing wheel, and a cutting edge feeding means of the polishing wheel, and the rotational driving means of the polishing wheel has a load current detecting means on the basis of end face contact of the substrate, and a compensating means of a load current generated by contact of groove side faces of an abrasion groove formed in the polishing wheel with the substrate.

[Fig. 1]